

## Assembly of III-V Microdisk Lasers on Silicon Using Lateral-Field Optoelectronic Tweezers

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**Abstract** A room-temperature optofluidic assembly process to integrate III-V microdisk lasers on a silicon chip is demonstrated. The assembly is accomplished using lateral-field optoelectronic tweezers, which achieves a placement accuracy of approximately  $\pm 0.25 \mu\text{m}$ .

### Introduction

Silicon photonics enables intimate integration of CMOS electronics and optoelectronic components. However, a challenge is the integration of semiconductor lasers on silicon. Silicon Raman lasers [1, 2] require external optical pumps. The growth temperature of heteroepitaxy ( $> 400^\circ\text{C}$ ) is usually too high for post-CMOS processing [3]. Low-temperature ( $300^\circ\text{C}$ ) wafer bonding techniques [4] present additional challenges on fully-processed CMOS wafers, as the silicon bonding surfaces are buried underneath layers of electrical interconnects. We demonstrate an optofluidic device capable of integrating thin ( $0.2 \mu\text{m}$ ), compact ( $5$  to  $10 \mu\text{m}$  in diameter) III-V microdisk lasers on patterned Si wafers in a room-temperature post-CMOS process. The assembly process is realized using lateral-field optoelectronic tweezers (LOET), and enables the integration of compound semiconductor components with CMOS circuits.

### Assembly of III-V Microdisk Lasers on Silicon

Multiple quantum-well III-V microdisk lasers are fabricated on III-V wafers, released in solution, and assembled on silicon pedestals using LOET. The LOET is directly fabricated on a Si wafer, and consists of an array of interdigitated photosensitive electrodes of amorphous silicon (a-Si) (Fig. 1a). Silicon pedestals are centered in the  $5\text{-}\mu\text{m}$ -wide gaps between the LOET electrodes.

The LOET electrodes create an optically-induced dielectrophoretic force, which is controlled by voltage applied across the electrodes and the position of optical patterns on the light-sensitive a-Si layer [5]. The highest forces are in the illuminated areas near the electrode edges (Fig. 1b). Microdisks are attracted to the illuminated areas, and self-align in the gap between the electrodes. Moving the optical patterns allows transportation of the microdisks along the length of the electrodes. Once the disks are aligned over a pedestal, the applied voltage is increased to hold the disks in place as the solution dries. Ethanol is used to minimize surface tension forces during drying. After drying, the a-Si layer is removed by  $\text{XeF}_2$  etching at  $40^\circ\text{C}$  to prevent interfering with the optical mode of the microdisk. The disks are aligned with an accuracy of approximately  $\pm 0.25 \mu\text{m}$  (Fig. 2a). This can be further improved by optimizing the optical imaging system.

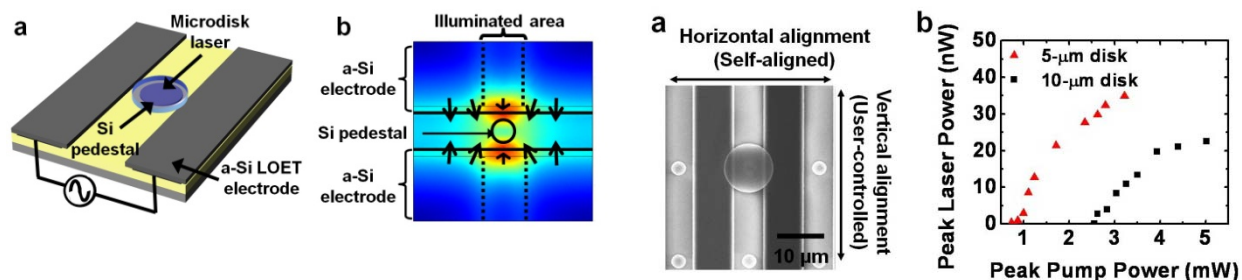


Fig. 1 (a) Schematic of integrated LOET for microdisk laser assembly. The LOET electrodes allow optical patterns to control the assembly of III-V microdisks on silicon pedestals. (c) Finite-element simulation of the electric field profile across the LOET electrodes. The arrows show the direction of the optically-induced force.

Fig. 2. (a) An assembled  $10\text{-}\mu\text{m}$ -diameter microdisk. (b) Peak laser power versus peak pump power. The threshold pump powers for  $5\text{-}\mu\text{m}$ - and  $10\text{-}\mu\text{m}$ -diameter disks are  $0.85 \text{ mW}$  and  $2.5 \text{ mW}$ , respectively. The actual optical power is higher since only scattered light from the top of the disk is measured.

The assembled microdisk lasers are optically pumped by 0.5- $\mu$ s pulses with a 20-kHz repetition rate (1% duty cycle) using a 780-nm diode laser. At room temperature, the 5- and 10- $\mu$ m-diameter microdisks achieve single-mode lasing at wavelengths of 1559 nm and 1586 nm, at threshold pump powers of 0.85 mW and 2.5 mW, respectively (Fig. 2b).

### References

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